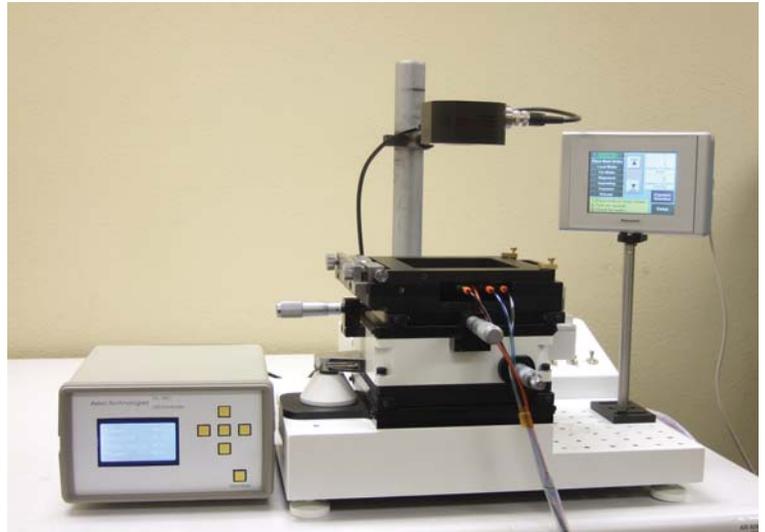


NANOLITHOGRAPHY MADE SIMPLE!

NANOIMPRINT TECHNOLOGY PLATFORM FOR RESEARCH AND DEVELOPMENT

Nanolithosolution provides a revolutionary one-step, Auto Release™ nanoimprint lithography solution with sub-10 nm resolution and accurate overlay alignment. This technology is built on years of research at HP Labs. Our technology is so simple to implement, essentially everyone with a microlithography process can upgrade to nanoscale lithography with no disruption to their regular process flow and facility. And our solution is the most cost-effective in the industry. Our process has been proven by some of the world leading institutes in state-of-the-art nanotechnology research to develop many ground-breaking applications



EQUIPMENT

Nanolithosolution's Nanoimprint Technology Platform (NTP-100) is a standalone include a nanoimprint module with AutoRelease™ function, a automatic imprint controller. It provides same proven robust performance as our early products. In addition, NTP a customized LED UV exposure source, and a position fixture upgradable to nanoposition capability. The NTP provides position interfaces for customized the configuration, special imaging system, platform for external probes. Our solution provides a state of are nanoimprint solution for anyone using a traditional photolithography process. Our is scalable with many upgradable functions, specially design for university research environments.

NANOIMPRINT MODULE: AR-NIM-100N

The nanoimprint module is a set of equipment that fits into NTP-100 like a typical wafer holder and mask holder. It precisely holds the imprint mold and wafer and accurately performs nanoimprinting and separation of the imprint mold with one easy step.

NANOIMPRINT CONTROLLER: AR-IMC-100

The nanoimprint controller provides semiautomatic control of the imprinting process. The program directs the user through a series of simple and straightforward steps to complete the entire procedure.

ADVANTAGES

- Simple and Robust process: proven through the research of world-leading institutions.
- Precision alignment: mask alignment is limited only by optical aligner capability.
- Easy to use: a person familiar with semiconductor processes can be trained in a few hours.
- No disruption with existing process: No extra equipment footprint required.

APPLICATIONS

optical devices, displays, data storage, biotech, semiconductor ICs, chemical synthesis, and advanced materials.